

#4/4

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:	)	Examiner: Unknown
PIOCHED 4 -1	)	
FISCHER et al.	)	Art Unit: 2817
Application No. 10/077,072	)	7Ht OHt. 2017
, , , , , , , , , , , , , , , , , , ,	)	Docket No. P0877
Filed: February 14, 2002	)	
	)	Date: April 8, 2002
For: A Plasma Processing Apparatus	)	
And Method for Confining An RF Plasma	)	
Under Very High Gas Flow and RF Power	)	
Density Conditions (As Amended)	)	
	)	
	_)	

CERTIFICATE OF MAILING
I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, DC 20231 on April 8, 2002.

Signed: Ahouen Lillay
Sharon D. Tillery

## **Preliminary Amendment**

Commissioner for Patents Box Non-Fee Amendment Washington, DC 20231

Sir:

Please enter the following preliminary amendment prior to examining the above referenced patent application.

## IN THE TITLE

Please change the title from "A Plasma Processing Apparatus and Method" to
--A Plasma Processing Apparatus and Method for Confining an RF Plasma Under

Very High Gas Flow and RF Power Density Conditions--